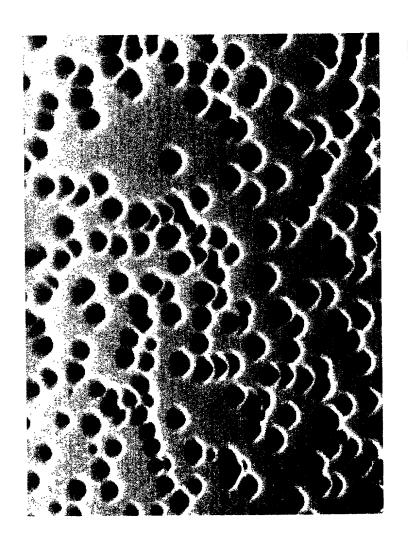
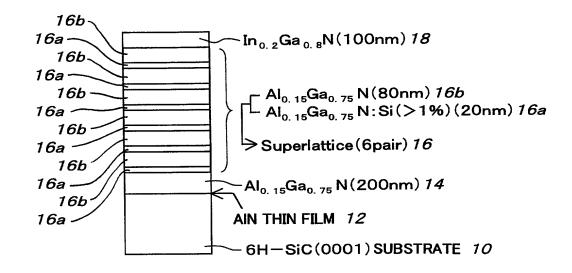
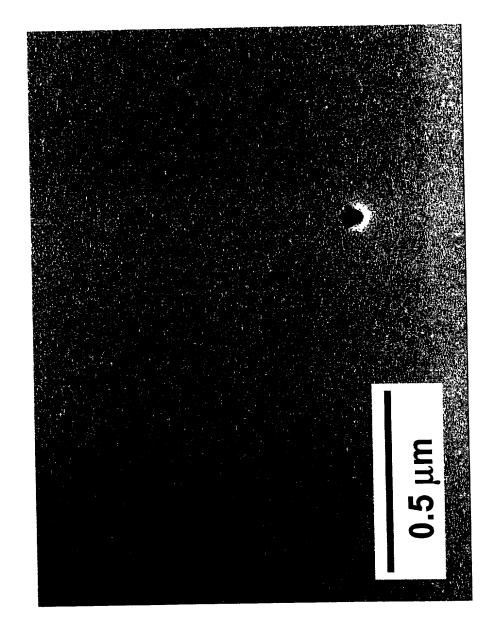


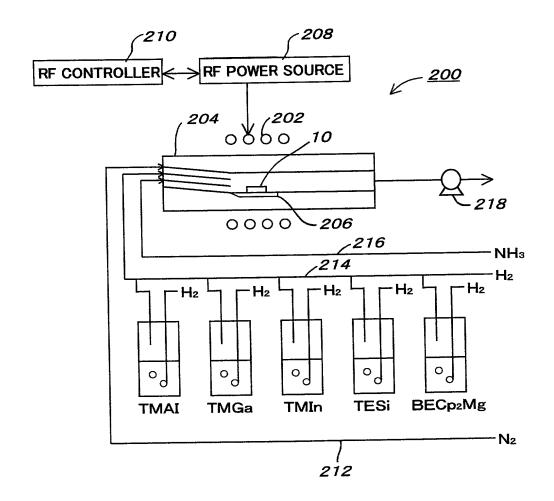
FIG. 2



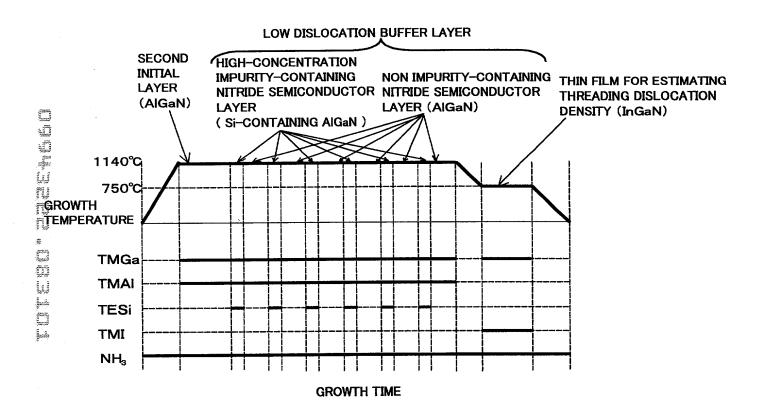
0.5 µm



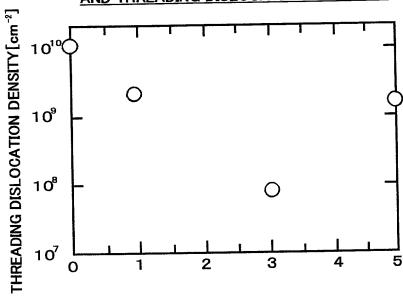




TIMING CHART FOR INTRODUCING MATERIAL GASES

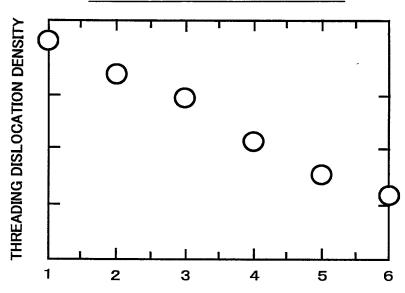


RELATIONSHIP BETWEEN TESI FLOW RATE AND THREADING DISLOCATION DENSITY

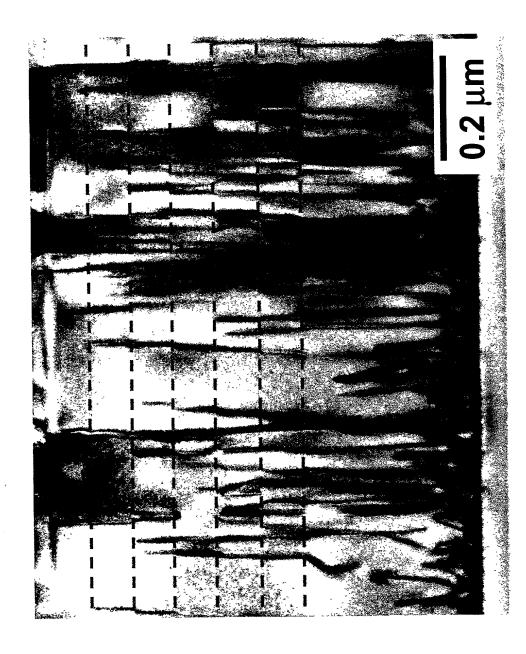


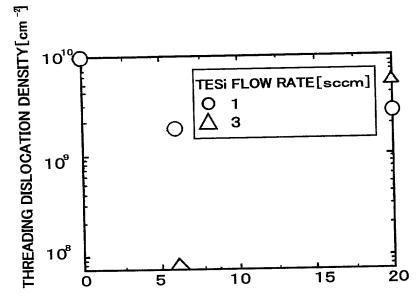
TESi FLOW RATE[sccm]

RELATIONSHIP BETWEEN PERIOD OF SUPERLATTICE BUFFER LAYER AND THREADING DISLOCATION DENSITY



PERIODICITY OF SUPERLATTICE BUFFER LAYER (NUMBER OF TIMES)





PERIODICITY OF SUPERLATTICE BUFFER LAYER (NUMBER OF TIMES)

NITRIDE SEMICONDUCTOR HFET
(Heterostructure Field Effect Transistor)
(EXAMPLE, AIGAN/GaN-HFET)

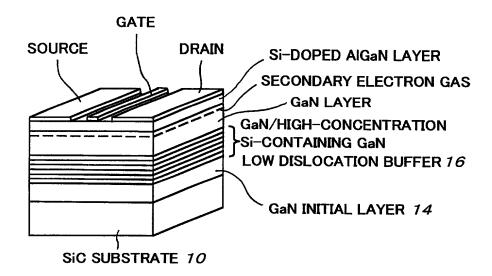


FIG. 12

NITRIDE SEMICONDUCTOR LASER DIODE (EXAMPLE, InGaN LASER)

